

Title (en)  
ION IMPLANTER OPERATING IN PULSED PLASMA MODE

Title (de)  
IN GEPULSTEM PLASMA-MODUS FUNKTIONIERENDE IONEN-IMPLANTIERUNGSVORRICHTUNG

Title (fr)  
IMPLANTEUR IONIQUE FONCTIONNANT EN MODE PLASMA PULSE

Publication  
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Application  
**EP 05777129 A 20050614**

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Abstract (en)  
[origin: WO2006003322A2] The invention relates to an ion implanter (IMP) comprising a pulsed plasma source (SPL), a substrate support plate (PPS) and a power supply (ALT) for said plate. The inventive implanter also comprises a capacitor C which is connected directly to the earth (E) and which is mounted downstream of the plate power supply (ALT). The invention also relates to a method of using said implanter.

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Citation (search report)  
See references of WO 2006003322A2

Citation (examination)  
• EP 1111084 A1 20010627 - AXCELIS TECH INC [US]  
• US 4937205 A 19900626 - NAKAYAMA ICHIRO [JP], et al

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